# High thermoelectric performance of Si-Ge alloy by modifying the electronic structure

<sup>o(PC)</sup>Muthusamy Omprakash<sup>1</sup>, Saurabh Singh<sup>1,3</sup>, Masahiro Adachi<sup>2</sup>, Yoshiyuki

Yamamoto<sup>2</sup>, Tsunehiro Takeuchi<sup>1,3,4,5</sup>

<sup>1</sup>Research Center for Smart Energy Technology, Toyota Technological Institute, Nagoya 468-8511, Japan <sup>2</sup>Sumitomo Electric Industries, Ltd., Hyogo 664-0016, Japan.

<sup>3</sup> CREST, Japan Science and Technology Agency, Toyota Technological Institute, Tokyo 102-0076, Japan.

<sup>4</sup> MIRAI, Japan Science and Technology Agency, Toyota Technological Institute, Tokyo 102-0076, Japan.

<sup>5</sup> Institute of Innovation for Future Society, Nagoya University, Nagoya 464-8603, Japan.

E-mail: omprakashmuthusamy@gmail.com

## Introduction

In order to improve the figure of merit ZT, many strategies have been reported. For example, nano-structuring and modulation doping approach has been utilized to improve the thermoelectric properties of Si-Ge alloy by decreasing thermal conductivity without degrading the power factor [1].

Our previous studies revealed that B-doped Si-Ge-Au thin film and bulk sample possessed ZT value of 1.38 and 1.63 at 1000K. We found that the electron transport properties were constructively improved using Au-doping to form an impurity states near the valence band top, and B-doping to control the Fermi level. Very small thermal conductivity ~ 1.5  $Wm^{-1}K^{-1}$  was obtained due to nanograins. However, Au is an expensive element and more than ZT = 1.63 is required for improving efficiency. In the present study, we synthesized bulk noncrystalline B-doped Si-Ge alloy with other metal substitution, which is a cheap and non-toxic element. Thermoelectric properties (TE) of bulk nanocrystalline samples were investigated as a function of temperature 300 - 1000 K, respectively.

### **Experimental Procedure**

High purity metal (3 at.%) substituted Ge mother ingot was crushed into powders and sealed with the high purity Si (5N) and 3 at.% of boron in a Zirconia container with Zirconia balls in the glove box under pressurized Ar gas atmosphere. The mixed powders were milled at a speed of 600 rpm for 6 h. Afterwards, the powders were subsequently sintered with a relatively high pressure of 400 MPa at 1003 K for 4 h.

## **Results and discussion**

The powder XRD indicated that the single

phase of diamond structure was obtained after the ball-milling. The size of nano-crystals in the bulk sample was estimated to be 30 nm from the XRD peaks and the Scherrer equation. The large Seebeck coefficient of 360  $\mu V^{-1}K^{-1}$  at 1000 K was obtained presumably due to presence of sharp peaks near the valence band edge. The electrical resistivity was 4.5 mOcm at 1000 K. As a consequence, a very large power factor reaching 2.6  $\text{mWm}^{-1}\text{K}^{-2}$  together with low thermal conductivity 1.47 Wm<sup>-1</sup>K<sup>-1</sup> allow us to obtain high ZT = 1.8 at 1000 K, respectively as shown in Fig.1. The obtained ZT was higher than that of the previously reported Si-Ge-Au nanocomposites (ZT = 1.63) [2]. The TE properties of different at.% metal substituted *p*-type Si-Ge will be discussed.



**Figure 1** Figure of merit of B-doped Si-Ge with 3 at.% metal substituted nanocrystalline sample as a function of temperature.

### References

[1] N. Mingo et al., Nano Letters 9, 71, (2009).

[2] M. Omprakash et al., Jpn. J. Appl. Phys. 58, 125501 (2019).